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(57) ABSTRACT

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There is provided an excimer laser device capable of producing a stable oscillation even at a high repetition rate of 4 kHz. This gas laser device is comprised of a laser chamber having laser gas filled therein; a pair of main discharge electrodes arranged in the laser chamber; a cross-flow fan for circulating the laser gas within the laser chamber at least between the main discharge electrodes; and a diameter of the cross-flow fan is 150 mm or less, its peripheral speed being 25.0 m/s or more.

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